

UNITED STATES PATENT AND TRADEMARK OFFICE



UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/058,662	01/28/2002	Ryoichi Mukai	2500.66134	3822
	7590 07/16/2007		EXAM	INER ·
Patrick G. Burns, Esq. GREER, BURNS & CRAIN, LTD.			PIZIALI, ANDREW T	
Suite 2500 300 South Wacker Dr. Chicago, IL 60606		ART UNIT	PAPER NUMBER	
			1771	
			MAIL DATE	DELIVERY MODE
		•	07/16/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary 10/058,662 MUKAI, RYOICHI Examiner Art Unit					
Office Action Summary Examiner Art Unit					
Andrew T. Piziali 1771					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).					
Status					
1) Responsive to communication(s) filed on 14 June 2007.					
2a)⊠ This action is FINAL . 2b)□ This action is non-final.					
Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4)⊠ Claim(s) <u>1,4-6 and 19-23</u> is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.	Claim(s) is/are allowed.				
6)⊠ Claim(s) <u>1,4-6 and 19-23</u> is/are rejected.	☑ Claim(s) <u>1,4-6 and 19-23</u> is/are rejected.				
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or election requirement.					
Application Papers					
9) The specification is objected to by the Examiner.					
10)⊠ The drawing(s) filed on <u>5/26/05 & 1/28/02</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.					
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121	(d).				
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119					
12)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a)⊠ All b)□ Some * c)□ None of:					
1. Certified copies of the priority documents have been received.					
2. Certified copies of the priority documents have been received in Application No	2. Certified copies of the priority documents have been received in Application No				
3. Copies of the certified copies of the priority documents have been received in this National Stage					
application from the International Bureau (PCT Rule 17.2(a)).					
* See the attached detailed Office action for a list of the certified copies not received.					
Attachment(s)					
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date					
3) Information Disclosure Statement(s) (PTO/SB/08) 5) Notice of Informal Patent Application					

DETAILED ACTION

Response to Amendment

1. The amendment filed on 6/14/2007 has been entered.

Claim Rejections - 35 USC § 112

- 2. The following is a quotation of the first paragraph of 35 U.S.C. 112:
 - The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.
- 3. Claims 22 and 23 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claims contain subject matter that was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor, at the time the application was filed, had possession of the claimed invention.

The specification fails to teach or suggest a part of the seed crystal layer interposed or existing between the metallic islands. The figures also fail to show these claim limitations. Although Figures 2, 10 and 11 illustrate grain areas (29) as perfectly shaped rectangles due to perfectly straight grain boundaries (31), the figures and/or specification do not teach or suggest that the grains grow in perfect rectangular form around the nucleation site (27). The Figures merely illustrate the approximate area within which the grains partially occupy.

Page 3

Art Unit: 1771

4. Claims 22 and 23 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claims contain subject matter that was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention.

According to the teaching of USPN 5,846,648 to Chen et al., when a grain grows on a spatially spaced nucleation site, the grain does not contain the nucleation site, rather, the grain grows vertically on top of the nucleation site and the size and spacing of the nucleation site dictates the size and spacing of the corresponding grain (see column 8, lines 15 through column 9, line 53, and Figure 2). Thus, the current figures and the current specification convey to one skilled in the relevant art that each crystal grain grows vertically over a nucleation site rather than growing outwardly in every direction (into a perfect rectangular shape) and contacting each other at (perfectly straight) grain boundaries.

Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 1, 4-6 and 19-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over USPN 5,846,648 to Chen in view of USPN 6,602,621 to Matsunuma.

Art Unit: 1771

Regarding claims 1, 4, 6 and 19-23, Chen discloses a polycrystalline structure film comprising metallic islands (74) formed on a surface of a substrate (12), a seed crystal layer (24) containing crystal grains (76) having grown from a corresponding one of the metallic islands, and a magnetic crystal layer (16) containing magnetic crystal grains (78), each of the magnetic crystal grains having grown from a corresponding one of the crystal grains of the seed crystal layer (see entire document including Figure 2, column 8, lines 15-48, column 9, lines 14-65, column 10, lines 7-39, column 11, lines 11-22, the paragraph bridging columns 11 and 12, and column 16, lines 9-46).

Figure 2 of Chen does not appear to illustrate the islands (74) as being physically spaced from each other, but Chen specifically discloses that the islands (also known as the nucleation sites, see column 17, lines 57-60) are to be spaced to provide a method for optimizing the segregation of segregant material at the grain boundaries in the magnetic layer (column 8, lines 39-48 and column 18, lines 7-16).

In the event that it is shown that Chen does not disclose the claimed physically spaced islands with sufficient specificity, the invention is obvious because Chen discloses that it is understood by one of ordinary skill in the art that the spacing determines properties such as high coercivity, high squareness, low noise, proper segregation spacing, and improved overwrite (column 2, lines 24-31, column 8, lines 15-48, column 9, lines 14-26, column 12, lines 29-41, and column 16, lines 9-46). It would have been obvious to one having ordinary skill in the art at the time the invention was made to physically space the islands, because the spacing determines properties such as high coercivity, high squareness, low noise, proper segregation spacing, and

Art Unit: 1771

improved overwrite, and because it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art.

Chen does not appear to specifically mention the metallic islands (nucleation sites) including atoms of at least one metallic element and molecules of a compound selected from an oxide or a nitride, but Matsunuma discloses that it is known in the magnetic recording art to use a material including atoms of at least one metallic element, such as Pt and Co, and molecules of a compound, such as SiN (see entire document including column 4, lines 18-65). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Pt, Co, and SiN, as taught by Matsunuma, because the resulting structure would possess reduced transition noise and/or high S/N and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Regarding claim 6, Matsunuma discloses that the compound may be present in a range of between 5at% and 20at% (column 4, lines 42-65).

Regarding claims 19 and 20, Chen discloses that each or the crystal grains (78) of the magnetic crystal layer (16) are separated from another crystal grain of the magnetic crystal layer at a grain boundary (see Figure 2). Chen also discloses that the crystal grains of the magnetic crystal layer are made of cobalt and platinum (column 15, lines 5-10). Chen does not appear to specifically mention chromium atoms diffusing along the grain boundary, but considering that the crystal grains of the magnetic crystal layer comprise chromium (column 15, lines 5-10), and considering that the underlying intermediate layer is made of chromium atoms (column 11, lines

Art Unit: 1771

11-21), it appears that chromium atoms inherently diffuse along the grain boundary and form a wall of chromium atoms.

The Patent and Trademark Office can require applicants to prove that prior art products do not necessarily or inherently possess characteristics of claimed products where claimed and prior art products are identical or substantially identical, or are produced by identical or substantially identical processes; burden of proof is on applicants where rejection based on inherency under 35 U.S.C. § 102 or on prima facie obviousness under 35 U.S.C. § 103, jointly or alternatively, and Patent and Trademark Office's inability to manufacture products or to obtain and compare prior art products evidences fairness of this rejection, *In re Best, Bolton, and Shaw*, 195 USPQ 431 (CCPA 1977).

Regarding claims 22 and 23, Chen illustrates a part of the seed crystal layer being interposed or existing between the metallic islands (Figure 2).

7. Claims 1 and 19-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over USPN 5,846,648 to Chen in view of USPN 6,620,533 to Hikosaka.

Regarding claims 1 and 19-23, Chen discloses a polycrystalline structure film comprising metallic islands (74) formed on a surface of a substrate (12), a seed crystal layer (24) containing crystal grains (76) having grown from a corresponding one of the metallic islands, and a magnetic crystal layer (16) containing magnetic crystal grains (78), each of the magnetic crystal grains having grown from a corresponding one of the crystal grains of the seed crystal layer (see entire document including Figure 2, column 8, lines 15-48, column 9, lines 14-65, column 10, lines 7-39, column 11, lines 11-22, the paragraph bridging columns 11 and 12, and column 16, lines 9-46).

Art Unit: 1771

Figure 2 of Chen does not appear to illustrate the islands (74) as being physically spaced from each other, but Chen specifically discloses that the islands (also known as the nucleation sites, see column 17, lines 57-60) are to be spaced to provide a method for optimizing the segregation of segregant material at the grain boundaries in the magnetic layer (column 8, lines 39-48 and column 18, lines 7-16).

In the event that it is shown that Chen does not disclose the claimed physically spaced islands with sufficient specificity, the invention is obvious because Chen discloses that it is understood by one of ordinary skill in the art that the spacing determines properties such as high coercivity, high squareness, low noise, proper segregation spacing, and improved overwrite (column 2, lines 24-31, column 8, lines 15-48, column 9, lines 14-26, column 12, lines 29-41, and column 16, lines 9-46). It would have been obvious to one having ordinary skill in the art at the time the invention was made to physically space the islands, because the spacing determines properties such as high coercivity, high squareness, low noise, proper segregation spacing, and improved overwrite, and because it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art.

Chen does not appear to specifically mention the metallic islands (nucleation sites) including atoms of at least one metallic element and molecules of a compound selected from an oxide or a nitride, but Hikosaka discloses that it is known in the magnetic recording art to use a material including atoms of at least one metallic element, such as Pt and Co, and molecules of a compound, such as an oxide or nitride (see entire document including claim 3). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Pt, Co, and an oxide or nitride, as taught

Art Unit: 1771

by Hikosaka, because the resulting structure would possess improved recording resolution, improved resistance to thermal decay, and/or high S/N and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Regarding claims 19 and 20, Chen discloses that each or the crystal grains (78) of the magnetic crystal layer (16) are separated from another crystal grain of the magnetic crystal layer at a grain boundary (see Figure 2). Chen also discloses that the crystal grains of the magnetic crystal layer are made of cobalt and platinum (column 15, lines 5-10). Chen does not appear to specifically mention chromium atoms diffusing along the grain boundary, but considering that the crystal grains of the magnetic crystal layer comprise chromium (column 15, lines 5-10), and considering that the underlying intermediate layer is made of chromium atoms (column 11, lines 11-21), it appears that chromium atoms inherently diffuse along the grain boundary and form a wall of chromium atoms.

Regarding claims 22 and 23, Chen illustrates a part of the seed crystal layer being interposed or existing between the metallic islands (Figure 2).

8. Claims 1, 4, 19-20, 22 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over USPN 5,846,648 to Chen in view of USPN 5,631,094 to Ranjan.

Regarding claims 1, 4, 19-20, 22 and 23, Chen discloses a polycrystalline structure film comprising metallic islands (74) formed on a surface of a substrate (12), a seed crystal layer (24) containing crystal grains (76) having grown from a corresponding one of the metallic islands, and a magnetic crystal layer (16) containing magnetic crystal grains (78), each of the magnetic crystal grains having grown from a corresponding one of the crystal grains of the seed crystal

Art Unit: 1771

layer (see entire document including Figure 2, column 8, lines 15-48, column 9, lines 14-65, column 10, lines 7-39, column 11, lines 11-22, the paragraph bridging columns 11 and 12, and column 16, lines 9-46).

Figure 2 of Chen does not appear to illustrate the islands (74) as being physically spaced from each other, but Chen specifically discloses that the islands (also known as the nucleation sites, see column 17, lines 57-60) are to be spaced to provide a method for optimizing the segregation of segregant material at the grain boundaries in the magnetic layer (column 8, lines 39-48 and column 18, lines 7-16).

In the event that it is shown that Chen does not disclose the claimed physically spaced islands with sufficient specificity, the invention is obvious because Chen discloses that it is understood by one of ordinary skill in the art that the spacing determines properties such as high coercivity, high squareness, low noise, proper segregation spacing, and improved overwrite (column 2, lines 24-31, column 8, lines 15-48, column 9, lines 14-26, column 12, lines 29-41, and column 16, lines 9-46). It would have been obvious to one having ordinary skill in the art at the time the invention was made to physically space the islands, because the spacing determines properties such as high coercivity, high squareness, low noise, proper segregation spacing, and improved overwrite, and because it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art.

Chen does not appear to specifically mention the metallic islands (nucleation sites) including atoms of at least one metallic element and molecules of a compound selected from an oxide or a nitride, but Ranjan discloses that it is known in the magnetic recording art to use a material including atoms of at least one metallic element, such as Ni, and molecules of a

Art Unit: 1771

compound, such as Al₂O₃ (see entire document including column 6, lines 10-28). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Ni₃P and Al₂O₃, as taught by Ranjan, because the resulting structure would possess improved corrosion resistance, higher coercivity, higher saturation magnetization, and/or higher squareness, and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Regarding claims 19 and 20, Chen discloses that each or the crystal grains (78) of the magnetic crystal layer (16) are separated from another crystal grain of the magnetic crystal layer at a grain boundary (see Figure 2). Chen also discloses that the crystal grains of the magnetic crystal layer are made of cobalt and platinum (column 15, lines 5-10). Chen does not appear to specifically mention chromium atoms diffusing along the grain boundary, but considering that the crystal grains of the magnetic crystal layer comprise chromium (column 15, lines 5-10), and considering that the underlying intermediate layer is made of chromium atoms (column 11, lines 11-21), it appears that chromium atoms inherently diffuse along the grain boundary and form a wall of chromium atoms.

Regarding claims 22 and 23, Chen illustrates a part of the seed crystal layer being interposed or existing between the metallic islands (Figure 2).

Response to Arguments

9. Applicant's arguments filed 6/14/2007 have been fully considered but they are not persuasive.

The applicant disputes examiner's assertion that Chen discloses that the nucleation sites may be formed of any material that allows for the epitaxial growth of the recording layer. In response, the examiner has deleted the disputed statement. Regardless, the examiner maintains the same grounds of rejection.

The applicant asserts that the applied prior art fails to teach or suggest a composition for the islands. The examiner respectfully disagrees. Matsunuma, Hikosaka, and Ranjan each disclose specific compositions for the islands:

1) Chen does not appear to specifically mention the metallic islands (nucleation sites) including atoms of at least one metallic element and molecules of a compound selected from an oxide or a nitride, but Matsunuma discloses that it is known in the magnetic recording art to use a material including atoms of at least one metallic element, such as Pt and Co, and molecules of a compound, such as SiN (see entire document including column 4, lines 18-65). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Pt, Co, and SiN, as taught by Matsunuma, because the resulting structure would possess reduced transition noise and/or high S/N and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Art Unit: 1771

Chen does not appear to specifically mention the metallic islands (nucleation sites including atoms of at least one metallic element and molecules of a compound selected from an oxide or a nitride, but Hikosaka discloses that it is known in the magnetic recording art to use a material including atoms of at least one metallic element, such as Pt and Co, and molecules of a compound, such as an oxide or nitride (see entire document including claim 3). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Pt, Co, and an oxide or nitride, as taught by Hikosaka, because the resulting structure would possess improved recording resolution, improved resistance to thermal decay, and/or high S/N and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Page 12

Chen does not appear to specifically mention the metallic islands (nucleation sites including atoms of at least one metallic element and molecules of a compound selected from an oxide or a nitride, but Ranjan discloses that it is known in the magnetic recording art to use a material including atoms of at least one metallic element, such as Ni, and molecules of a compound, such as Al₂O₃ (see entire document including column 6, lines 10-28). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Ni₃P and Al₂O₃, as taught by Ranjan, because the resulting structure would possess improved corrosion resistance, higher coercivity, higher saturation magnetization, and/or higher squareness, and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Art Unit: 1771

The substitution of known equivalent structures involves only ordinary skill in the art. *In* re Fout 213 USPQ 532 (CCPA 1982); *In* re Susi 169 USPQ 423 (CCPA 1971); *In* re Siebentritt 152 USPQ 618 (CCPA 1967); In re Ruff 118 USPQ 343 (CCPA 1958). When a patent claims a structure already known in the prior art that is altered by the mere substitution of one element for another known in the field, the combination must do more than yield a predictable result. **KSR** v. **Teleflex**

Page 13

The applicant asserts that Chen teaches that bringing the islands together is desirable. The examiner respectfully disagrees. Figure 2 of Chen does not appear to illustrate the islands (74) as being physically spaced from each other, but Chen specifically discloses that the islands (also known as the nucleation sites, see column 17, lines 57-60) are to be spaced to provide a method for optimizing the segregation of segregant material at the grain boundaries in the magnetic layer (column 8, lines 39-48 and column 18, lines 7-16).

The applicant asserts that there is no motivation to incorporate the system of Ranjan into the system of Chen. The examiner contends that the rejection does not rely on such incorporation. Rather, Ranjan simply teaches that would have been obvious to one having ordinary skill in the art at the time the invention was made to make the metallic islands from any suitable material, such as Ni₃P and Al₂O₃, because the resulting structure would possess improved corrosion resistance, higher coercivity, higher saturation magnetization, and/or higher squareness, and because it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability and desired characteristics.

Art Unit: 1771

The applicant asserts that Ranjan is non-analogous art because the nucleation layer is formed on substrate material called an "underlayer" rather than a material called a "substrate." The applicant also asserts that Ranjan is non-analogous art because Ranjan allegedly does not include discrete islands. The examiner respectfully disagrees. It has been held that a prior art reference must either be in the field of applicant's endeavor or, if not, then be reasonably pertinent to the particular problem with which the applicant was concerned, in order to be relied upon as a basis for rejection of the claimed invention. See *In re Oetiker*, 977 F.2d 1443, 24 USPQ2d 1443 (Fed. Cir. 1992). In this case, Ranjan is in the field of applicant's endeavor, which is magnetic recording media.

Conclusion

10. Applicant's amendment necessitated the new grounds of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Art Unit: 1771

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Andrew T. Piziali whose telephone number is (571) 272-1541.

The examiner can normally be reached on Monday-Friday (8:00-4:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Terrel Morris can be reached on (571) 272-1478. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

atp

ANDREW PIZIALI PRIMARY EXAMINER

7/10/07

Page 15